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PATENT APPLICATION

1 /30

Aug 2 2 2005

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re United States Patent Application of:

Docket No.:

ATMI-668 (7493)

Applicants:

RATH, Melissa K., et al.

Conf. No.:

4823

Application No.:

10/792,038

Art Unit:

1752

Date Filed:

March 3, 2004

**Examiner:** 

LE, Hoa Van

Title:

COMPOSITION AND

PROCESS FOR POST-ETCH

REMOVAL OF

PHOTORESIST AND/OR SACRIFICIAL ANTI-REFLECTIVE MATERIAL

DEPOSITED ON A

SUBSTRATE

**Customer No.:** 

**FACSIMILE TRANSMISSION CERTIFICATE** 

ATTN: Examiner Hoa Van Le Fax No. (571) 273-8300

I hereby certify that this document is being filed in the United States Patent and Trademark Office, via facsimile transmission to Mail Stop Amendment, Commissioner for Patents, PO Box 1450, Alexandria, VA 22313-1450, on August 22, 2005 to United States Patent and Trademark Office facsimile transmission number (571) 273-8300.

> Number of Pages Tristan A. Fuierer August 22, 2005

AMENDMENT RESPONDING TO JUNE 2, 2005 OFFICE ACTION IN UNITED STATES PATENT APPLICATION NO. 10/792,038

Date

Mail Stop Amendment Commissioner for Patents PO Box 1450 Alexandria, VA 22313-1450

08/22/2005 TL0111 00000034 10792038

Sir:

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This responds to the June 2, 2005 Office Action in the above-identified application.

## PATENT APPLICATION

Please amend the claims of the application as set out in the following Section I (Amendments to the Claims).

Remarks addressing the substance of the June 2, 2005 Office Action are set out in the Section II (Remarks) hereof.